CLAIMS

1. A composition for depositing a tungsten film or tungsten-containing film by a chemical vapor deposition or atomic layer deposition process, the composition comprising:

   at least 90% by weight or greater of β- WCl_6

   wherein the β- WCl_6 has a controlled particle size imparted by a fluidization process.

2. The composition of claim 1, wherein the composition comprises at least 95% by weight or greater of β- WCl_6 and 5% by weight or less of α- WCl_6.

3. The composition of claim 2, wherein the composition further comprises 1% by weight or less of $WOCl_4$.

4. The composition of claim 1, wherein the composition comprises at least 99% by weight or greater of β- WCl_6 and 1% by weight or less of α- WCl_6.

5. The composition of claim 4, wherein the composition comprises at least 99.9% by weight or greater of β- WCl_6.

6. A delivery system for depositing a tungsten film or tungsten-containing film comprising:

   a composition comprising at least 90% by weight or greater of β-WCl_6;

   a vessel; and

   wherein the composition is inside the vessel.

7. The delivery system of claim 6, wherein the composition comprises at least 95% by weight or greater of β- WCl_6 and 5% by weight or less of α- WCl_6.

8. The delivery system of claim 6, wherein the composition comprises at least 99% by weight or greater of β- WCl_6 and 1% by weight or less of α- WCl_6.

9. The delivery system of claim 6, wherein the composition comprises at least 99.9% by weight or greater of β- WCl_6.